

TURBERFIELD, A. et al  
Serial No. unknown

10400-74

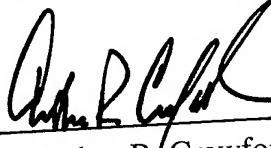
REMARKS

Attached hereto is a marked-up version of the changes made to the specification and claims by the current amendment. The attached page(s) is captioned "Version With  
Markings To Show Changes Made."

Respectfully submitted,

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VERSION WITH MARKINGS TO SHOW CHANGES MADE

IN THE SPECIFICATION

Page 1, before the first line, please insert as a separate paragraph:

This application is the US national phase of international application

PCT/GB00/03602 filed 20 September 2000, which designated the US.

IN THE CLAIMS

7. A method of fabricating a porous filter element according to any one of the preceding claims 1, wherein the regions extend in a straight line from a first side of said photosensitive material to a second, opposite side of said material.

8. A method of fabricating a porous filter element according to any one of the preceding claims 1, wherein the step of treating the exposed photosensitive material to selectively remove regions thereof comprises removing regions having an exposure below a predetermined level.

9. A method of fabricating a porous filter element according to any one of the preceding claims 1, wherein the step of treating the exposed photosensitive material to selectively remove regions thereof comprises removing regions having an exposure above a predetermined level.

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10. A method of fabricating a porous filter element according to any one of the preceding claims 1, wherein the pattern is substantially non-varying through the depth of the material whereby said regions have a constant cross-section through the material.

11. A method of fabricating a porous filter element according to any one of claims 1 to 9, wherein the pattern varies through the depth of the material to vary the cross-section of said regions through the depth of the material.

12. A method of fabricating a porous filter element according to claim 10 or 11, wherein the pattern repeats across the material perpendicular to the depth direction to create in the material a regular array of identical regions which extend through the depth of the material.

13. A method of fabricating a porous filter element according to any one of the preceding claims 1, wherein the material is a mixture of an epoxy resin and a photoacid generator.

14. A method of fabricating a porous filter element according to any one of the preceding claims 1, wherein the material to be exposed is in the form of a thin film.

15. A method of fabricating a porous filter element according to ~~any one~~ of the preceding claims 1 wherein the photosensitive material comprises a plurality of regions of different composition such that the different regions react differently to exposure followed by treatment.

17. A method of fabricating a porous filter element according to ~~any one~~ of the preceding claims 1, comprising the further step of using said treated material as a lost mould to form a porous filter element.

20. A method according to ~~any one of the preceding claims~~ 1 wherein the exposure time and/or intensity of the e.m. radiation is set selectively in accordance with the desired size of the regions.

21. A porous filter element made by the method of ~~any one of the preceding claims~~ 1.